



## Photoplotter

### Fabrication of Film Photomasks

The Filmstar Photoplotter, using a laser-diode of 670 nm wavelength, allows the fabrication of film photomasks needed for photolithography processes.

With a line precision down to 5µm, we can print film photomasks on large areas (230 mm x 360 mm) in house, speeding up the fabrication of sample by photolithography process.

### Technical specifications:

- Light source: Laser diode 670nm (red)
- Substrate maximum size: 250 mm x 380 mm
- Maximum exposure size: 230 mm x 360 mm
- Resolution:
  - X: 1625, 2032, 3251, 4064, 6502, 8128, 1656 dpi
  - Y: 25400 dpi
- Graphical resolution:
  - Finest point/ Finest line: 5 µm
  - Finest space between 2 lines: 10 µm
  - Finest space between 2 areas: 18 µm
  - Finest incise spot diameter: 25 µm
- Maximum file size : 256 MB
- Speed: 3 different plot speeds for either high precision or less time consumption (7 mm/min of film width at 2032 dpi)
- Data formats compatible: Gerber, Extended Gerber, Hi-Res BMP

### Software available:

- BMP converter to FPF file (FPF photoplotter final file)
- Gerber converter to FPF file
- FPF viewer

### Material available:

- Red light sensitive film photomasks: Idealine RPF line film (AGFA)
- Developer and fixer from Bungard Elektronik



### Equipment financed by: